	Hits	Search Text	DBs
1	3	(hard near5 mask$3) and capacitor and ((photosensitive near5 sol$3gel) or ((titanium or Ti) near7 sol$3gel) or (Ti$2Al near5 organic near4 gel) or (titanium near3 alumin$3 near4 sol$3gel)) and ((photoresist or resist or photo$3cur$4 or (radiation near5 sensitive)) same (pattern$3 or expos$3 or illuminat$3 or irradiat$3)) and ((thermal$3 near5 (decompos$5 or treat$5)) or heat$4 or bak$4) and (etch$3 same pattern$3 same ((hard near5 mask) or (etch$3resist$3 near5 mask$3)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
2	3	capacitor and ((photosensitive near5 sol$3gel) or ((titanium or Ti) near7 sol$3gel) or (Ti$2Al near5 organic near4 gel) or (titanium near3 alumin$3 near4 sol$3gel) or TiOEt) and ((photoresist or resist or photo$3cur$4 or (radiation near5 sensitive)) same (pattern$3 or expos$3 or illuminat$3 or irradiat$3)) and ((thermal$3 near5 (decompos$5 or treat$5)) or heat$4 or bak$4) and (etch$3 same pattern$3 same ((hard near5 mask) or (etch$3resist$3 near5 mask$3)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
3	96	capacitor and (((photosensitive near5 sol$3gel) or ((titanium or Ti) near7 sol$3gel) or (Ti$2Al near5 organic near4 gel) or (titanium near3 alumin$3 near4 sol$3gel) or TiOEt or TEOS) same (photoresist or resist or photo$3cur$4 or (radiation near5 sensitive)) same (pattern$3 or expos$3 or illuminat$3 or irradiat$3)) and ((thermal$3 near5 (decompos$5 or treat$5)) or heat$4 or bak$4) and (etch$3 same pattern$3 same ((hard near5 mask) or (etch$3resist$3 near5 mask$3)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
4	60	capacitor and ((photosensitive near5 sol$3gel) or ((titanium or Ti) near7 sol$3gel) or (Ti$2Al near5 organic near4 gel) or (titanium near3 alumin$3 near4 sol$3gel) or TiOEt or sol$4gel) and ((photoresist or resist or photo$3cur$4 or (radiation near5 sensitive)) same (pattern$3 or expos$3 or illuminat$3 or irradiat$3)) and ((thermal$3 near5 (decompos$5 or treat$5)) or heat$4 or bak$4) and (etch$3 same pattern$3 same ((hard near5 mask) or (etch$3resist$3 near5 mask$3)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
5	3	capacitor and (((photosensitive near5 sol$3gel) or ((titanium or Ti) near7 sol$3gel) or (Ti$2Al near5 organic near4 gel) or (titanium near3 alumin$3 near4 sol$3gel) or TiOEt or sol$4gel) same (photoresist or resist or photo$3cur$4 or (radiation near5 sensitive)) same (pattern$3 or expos$3 or illuminat$3 or irradiat$3)) and ((thermal$3 near5 (decompos$5 or treat$5)) or heat$4 or bak$4) and (etch$3 same pattern$3 same ((hard near5 mask) or (etch$3resist$3 near5 mask$3)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
6	3	capacitor and (((photosensitive near5 sol$3gel) or ((titanium or Ti) near7 sol$3gel) or (Ti$2Al near5 organic near4 gel) or (titanium near3 alumin$3 near4 sol$3gel) or TiOEt or sol$4gel) same (photoresist or resist or photo$3cur$4 or (radiation near5 sensitive))) and (pattern$3 or expos$3 or illuminat$3 or irradiat$3) and ((thermal$3 near5 (decompos$5 or treat$5)) or heat$4 or bak$4) and (etch$3 same pattern$3 same ((hard near5 mask) or (etch$3resist$3 near5 mask$3)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
7	47	capacitor and (((photosensitive near5 sol$3gel) or ((titanium or Ti) near7 sol$3gel) or (Ti$2Al near5 organic near4 gel) or (titanium near3 alumin$3 near4 sol$3gel) or TiOEt or sol$4gel) same (photoresist or resist or photo$3cur$4 or (radiation near5 sensitive))) and (pattern$3 or expos$3 or illuminat$3 or irradiat$3) and ((thermal$3 near5 (decompos$5 or treat$5)) or heat$4 or bak$4) and (etch$3 same (pattern$3 or mask$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
8	1	(capacitor or (dielectric same top same bottom same electrode)) and ((photosensitive near5 sol$3gel) or ((titanium or Ti or Al or alumin$2m) near6 organic near3 sol$3gel)) and (mask near4 (hard or etch$4resist$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
9	6	(capacitor or (dielectric same top same bottom same electrode)) and ((photosensitive near5 sol$3gel) or ((titanium or Ti or Al or alumin$2m) near6 organic near3 sol$3gel))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
10	5	(capacitor or (dielectric same top same bottom same electrode)) and ((photosensitive near5 sol$3gel) or ((titanium or Ti) near6 organic near3 sol$3gel))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
11	95	(capacitor or (dielectric same top same bottom same electrode)) and ((photosensitive near5 sol$3gel) or ((titanium or Ti or Al or alumin$2m) same (organic near8 sol$3gel)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
12	1	(capacitor or (dielectric same top same bottom same electrode)) and ((photosensitive near5 sol$3gel) or ((titanium or Ti or Al or alumin$2m) same (organic near8 sol$3gel))) and ((gel or sol$4gel) same photosensitive same (mask or hard$4mask or (etch$4resist$4 near6 mask)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
13	1	(capacitor or (dielectric same top same bottom same electrode)) and ((photosensitive near5 sol$3gel) or ((titanium or Ti or Al or alumin$2m) same (organic near8 sol$3gel))) and ((gel or sol$4gel) same (photosensitive or (light near8 sensitiv$4)) same (mask or hard$4mask or (etch$4resist$4 near6 mask)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
14	52	((gel or sol$4gel) same (photosensitive or (light near8 sensitiv$4)) same (mask or hard$4mask or (etch$4resist$4 near6 mask)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
15	18	((organic or polymer$4) same (gel or sol$4gel) same (photosensitive or (light near8 sensitiv$4)) same (mask or hard$4mask or (etch$4resist$4 near6 mask)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
16	22	((organic or polymer$4 or organometal$3) same (gel or sol$4gel) same (photosensitive or (light near8 sensitiv$4)) same (mask or hard$4mask or (etch$4resist$4 near6 mask)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
17	75	(capacitor or (dielectric same top same bottom same electrode)) and (((photosensitive or organometallic) near5 sol$3gel) or ((titanium or Ti or Al or alumin$2m) same (organic near8 sol$3gel))) and (mask or pattern)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
18	47	capacitor and ((((photosensitive or organometal$4) near5 sol$3gel) or ((titanium or Ti) near7 sol$3gel) or (Ti$2Al near5 organic near4 gel) or (titanium near3 alumin$3 near4 sol$3gel) or TiOEt or sol$4gel) same (photoresist or resist or photo$3cur$4 or (radiation near5 sensitive))) and (pattern$3 or expos$3 or illuminat$3 or irradiat$3) and ((thermal$3 near5 (decompos$5 or treat$5)) or heat$4 or bak$4) and (etch$3 same (pattern$3 or mask$4))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
19	43	(capacitor or (dielectric same top same bottom same electrode)) and (((photosensitive or organometallic) near5 sol$3gel) or ((titanium or Ti or Al or alumin$2m) same (organic near8 sol$3gel))) and (mask or pattern) and ((heat$4 or thermal$4 or bak$4) same (treat$4 or convert$4 or react$4 or decomposition) same (oxygen or nitrogen or "N.sub.2" or "O. sub.2"))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
20	31	(capacitor or (dielectric same top same bottom same electrode)) same (((photosensitive or organometallic) near5 sol$3gel) or sol$3gel or ((titanium or Ti or Al or alumin$2m) same (organic near8 sol$3gel))) same (mask or hard$3mask)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
21	55	(pattern$4 same (capacitor or (dielectric same top same bottom same electrode))) and ((((photosensitive or organometallic) near5 sol$3gel) or sol$3gel or ((titanium or Ti or Al or alumin$2m) same (organic near8 sol$3gel))) same (mask or hard$3mask))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
22	10	((((photosensitive or organometallic) near5 sol$3gel) or sol$3gel or ((titanium or Ti or Al or alumin$2m) near6 (organic near8 sol$3gel))) same pattern$4 same (hardmask or (hard near4 mask)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
23	27	((((photosensitive or organometallic) near5 sol$3gel) or ((titanium or Ti or Al or alumin$2m) near6 (organic near8 sol$3gel))) same (pattern$4 or hardmask or (hard near4 mask)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
24	4	((((photosensitive or organometallic) near5 sol$3gel) or sol$4gel or ((titanium or Ti or Al or alumin$2m) near6 (organic near8 sol$3gel))) same hardmask)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
25	0	((((photosensitive or organometallic) near5 sol$3gel) or sol$4gel or ((titanium or Ti or Al or alumin$2m) near6 (organic near8 sol$3gel))) near14 ((etch$5resistant near5 mask) or hardmask))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
26	4	((((photosensitive or organometallic) near5 sol$3gel) or sol$4gel or ((titanium or Ti or Al or alumin$2m) near6 (organic near8 sol$3gel))) same ((etch$5resistant near5 mask) or hardmask))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
27	55	((((photosensitive or organometallic) near5 sol$3gel) or sol$4gel or ((titanium or Ti or Al or alumin$2m) near6 (organic near8 sol$3gel)))) and ((etch$5resistant near5 mask) or hardmask)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
28	9	((((photosensitive or organometallic) near5 sol$3gel) or sol$4gel) same (layer or deposit$4 or film or form$3) same capacitor same (photoresist or resist) same pattern$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
29	16	((((photosensitive or organo$4metallic) near7 sol$3gel) or sol$4gel) same ((titanium near4 alkoxide) or TiOEt or (Ti near4 alkoxide near4 acetate)) same (heat$4 or thermal$4 or bak$4) same (oxygen or nitrogen))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
30	3	((((photosensitive or organo$4metallic) near7 sol$3gel) or sol$4gel) same ((titanium near4 alkoxide) or TiOEt or (Ti near4 alkoxide near4 acetate)) same (heat$4 or thermal$4 or bak$4) same (photolithograph$6 or lithograph$6 or photoresist or resist))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
31	2	((((photosensitive or organo$4metallic) near7 sol$3gel) or sol$4gel) same ((titanium near4 alkoxide) or TiOEt or (Ti near4 alkoxide near4 acetate)) same (heat$4 or thermal$4 or bak$4) same capacitor) and (photolithograph$6 or lithograph$6 or photoresist or resist)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
32	10	((((photosensitive or organo$4metallic) near7 sol$3gel) or sol$4gel) same ((titanium near4 alkoxide) or TiOEt or (Ti near4 alkoxide near4 acetate)) same (heat$4 or thermal$4 or bak$4) same capacitor) and (photolithograph$6 or lithograph$6 or photoresist or resist or pattern$4)	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
33	4	capacitor and (((photosensitive near5 sol$3gel) or organo$4metallic or ((titanium or Ti) near7 sol$3gel) or (Ti$2Al near5 organic near4 gel) or (titanium near3 alumin$3 near4 sol$3gel) or TiOEt) same (photoresist or resist or photo$3cur$4 or (radiation near5 sensitive)) same (pattern$3 or expos$3 or illuminat$3 or irradiat$3)) and ((thermal$3 near5 (decompos$5 or treat$5)) or heat$4 or bak$4) and (etch$3 same pattern$3 same ((hard near5 mask) or (etch$3resist$3 near5 mask$3)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
34	1	430/330.ccls. and capacitor and (((photosensitive near5 sol$3gel) or ((titanium or Ti) near7 sol$3gel) or (Ti$2Al near5 organic near4 gel) or (titanium near3 alumin$3 near4 sol$3gel) or TiOEt or TEOS) same (photoresist or resist or photo$3cur$4 or (radiation near5 sensitive)) same (pattern$3 or expos$3 or illuminat$3 or irradiat$3)) and ((thermal$3 near5 (decompos$5 or treat$5)) or heat$4 or bak$4) and (etch$3 same pattern$3 same ((hard near5 mask) or (etch$3resist$3 near5 mask$3)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
35	1	430/322.ccls. and capacitor and (((photosensitive near5 sol$3gel) or ((titanium or Ti) near7 sol$3gel) or (Ti$2Al near5 organic near4 gel) or (titanium near3 alumin$3 near4 sol$3gel) or TiOEt or TEOS) same (photoresist or resist or photo$3cur$4 or (radiation near5 sensitive)) same (pattern$3 or expos$3 or illuminat$3 or irradiat$3)) and ((thermal$3 near5 (decompos$5 or treat$5)) or heat$4 or bak$4) and (etch$3 same pattern$3 same ((hard near5 mask) or (etch$3resist$3 near5 mask$3))))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB
36	1	430/320.ccls. and capacitor and (((photosensitive near5 sol$3gel) or ((titanium or Ti) near7 sol$3gel) or (Ti$2Al near5 organic near4 gel) or (titanium near3 alumin$3 near4 sol$3gel) or TiOEt or TEOS) same (photoresist or resist or photo$3cur$4 or (radiation near5 sensitive)) same (pattern$3 or expos$3 or illuminat$3 or irradiat$3)) and ((thermal$3 near5 (decompos$5 or treat$5)) or heat$4 or bak$4) and (etch$3 same pattern$3 same ((hard near5 mask) or (etch$3resist$3 near5 mask$3))))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB

	Hits	Search Text	DBs
37	6	"430"/$.ccls. and capacitor and (((photosensitive near5 sol$3gel) or ((titanium or Ti) near7 sol$3gel) or (Ti$2Al near5 organic near4 gel) or (titanium near3 alumin$3 near4 sol$3gel) or TiOEt or TEOS) same (photoresist or resist or photo$3cur$4 or (radiation near5 sensitive)) same (pattern$3 or expos$3 or illuminat$3 or irradiat$3)) and ((thermal$3 near5 (decompos$5 or treat$5)) or heat$4 or bak$4) and (etch$3 same pattern$3 same ((hard near5 mask) or (etch$3resist$3 near5 mask$3)))	US-PGPUB; USPAT; EPO; JPO; DERWENT; IBM_TDB